

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|--------|--|---|------------------|---------|------------------|
| L1 | 273364 | (expose or exposing or exposed or exposure) same (semiconductor adj laser) same (nanometer or nm) photographic | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:13 |
| L2 | 29452 | color adj photographic | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:13 |
| L3 | 29452 | 1 and 2 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:14 |
| L4 | 273378 | ((expose or exposing or exposed or exposure) same (semiconductor adj laser) same (nanometer or nm)) same3 photographic | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:16 |
| L5 | 273389 | ((expose or exposing or exposed or exposure) same (semiconductor adj laser) same (nanometer or nm)) same2 photographic | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:17 |
| L6 | 202 | ((expose or exposing or exposed or exposure) same (semiconductor adj laser) same (nanometer or nm)) same photographic | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 10:57 |
| L7 | 31486 | ((expose or exposing or exposed or exposure) same (semiconductor adj laser) same (nanometer or nm)) same2 (color adj photographic) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:17 |
| L8 | 11 | ((silver same chloride) or AgCl) same (gain adj size) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 11:14 |

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|-----|------|---|---|----|----|------------------|
| L9 | 11 | silver same chloride same (gain adj size) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 11:13 |
| L10 | 3307 | ((silver same chloride) or AgCl) same (grain adj size) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 11:16 |
| L11 | 74 | (silver or AgCl) same (grain adj size) same (chloride adj5 mol%) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 11:17 |
| S1 | 202 | (expose or exposing or exposed or exposure) same (semiconductor adj laser) same (nanometer or nm) same photographic | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/03/30 09:15 |